Photomask Japan 2021

Best Paper Award Winners

Best Oral Presentation:

Program No.	Presentation Title	Name	Affliation
3-2 [BACUS]	EUV attenuated phase shift mask: development and characterization of mask properties	Ikuya Fukasawa	HOYA Group LSI Division (Japan)
10-2	High-brightness LDP source for EUVL mask inspection	Kazuya Aoki	USHIO INC. (Japan)

Best Poster Presentation:

Program No.	Presentation Title	Name	Affliation
P-10	Hydrogen Damage Evaluation of Mo/Si Multilayer using High-Power EUV Irradiation Tool	Tetsuo Harada	University of Hyogo (Japan)